	GLAST 1996	**GLAST 1997**	**GLAST 1998**	**GLAST 1999**	**Baseline**
Wafer Size	4”	4”	6”	6”	6”
Sensor Size	6cmx6cm	6.4cm×6.4cm	6.4cm×10.7cm	9.5cm×9.5cm	9.2cmx9.2cm
Pitch	236um	194um	194um	208um	201um
Implant Width [um]	57	50	50	52	
Thickness	500um	400um	400um	400um	400um
Biasing	Punch Through	Poly-Si	Poly-Si	Poly-Si	Poly-Si
Bias Voltage	140V	100V	100V		
Current [nA/cm^2]		~2.5	~2.5	~1.7	
% bad strips		0.02	0.04	0.04	
# delivered	20?	296	256	35	n.a.
Use	BT’97	BTEM	BTEM		

Additional Suppliers

Micron (UK):
produced ~5 detectors 9.5cm x 9.5cm from 6” wafers with UK funds.
Leakage current of 55nA/cm^2 outside of our specs (~15nA/cm^2).
% of bad strips good.
No follow-up run.

STM (Italy):
has done a pilot run with 6” wafers, cost shared between INFN and SLAC.
Detectors break down before depletion.
% of bad strips ok.
Fabrication continues with new run.